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(54) **PHOTOSENSITIVE COMPOSITION FOR EUV LIGHT, PATTERN FORMATION METHOD, AND METHOD FOR MANUFACTURING ELECTRONIC DEVICE**

(57) Provided are a photosensitive composition for EUV light, which has a good Z-factor and is capable of forming a pattern having a suppressed bridge defect, a pattern forming method, and a method for manufacturing an electronic device. The photosensitive composition for EUV light includes a predetermined resin and a photoacid generator, or includes a predetermined resin having a repeating unit having a photoacid generating group, and satisfies Requirements 1 to 3,
Requirement 1: The A value determined by Formula (1) is 0.14 or more,

$$\text{Formula (1): } A = ([H] \times 0.04 + [C] \times 1.5 + [I] \times 39.5) / ([H] \times 1 + [C] \times 12 + [N] \times 1)$$

Requirement 2: The concentration of solid contents in the photosensitive composition for EUV light is 5.0% by mass or less,

Requirement 3: The content of the photoacid generator is 5% to 50% by mass with respect to the total solid content in the photosensitive composition for EUV light.

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